IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: STEGER

Examiner: UNKNOWN PRUCHMIC

Application No. 10/720,839

Group No. 2858 2859

Filed: 11/24/2003

Confirmation No. 3615

Title: METHODS AND APPARATUS FOR IN SITU SUBSTRATE TEMPERATURE

MONITORING

INFORMATION DISCLOSURE STATEMENT

US PATENT DOCUMENTS

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Examiner	Cite	Document Number	Publication Date	Name of Patentee or	Reference to Related Case
Initials	No.			Applicant	CLAST CL/Sh
SOC	L	6514376 BI	2003-02-04	Collins et al.	-1-
1	2	6605955 B1	2003-08-12	Costello et al.	-/-
	3	6635117 B1	2003-10-21	Kinnard et al.	- /-
-	4	4919542	1990-04-24	Nulman et al.	ALREADY CITY BY EXAM
	5	5200023	1993-04-06	Gifford et al.	-/-
	6	5229303	1993-07-20	Donnelly, Jr. et al.	-/-
	7	5388909	1995-02-14	Johnson et al.	-/-
	8	5467732	1995-11-21	Donnelly, Jr. Et al.	-/-
	9	5490728	1996-02-13	Schietinger et al.	-/-
	10	5568978	1996-10-29	Johnson et al.	-/-
	11	5660472	1997-08-26	Peuse et al.	-/-
	12	5683180	1997-11-04	De Lyon et al.	-/-
	13	5746513	1998-05-05	Renken	-/-
	14	5755511	1998-05-26	Peuse et al.	- -
	15	5769540	1998-06-23	Schietinger et al.	-/-
	16	5775808	1998-07-07	Pan	2/-
	17	5848842	1998-12-15	Peuse et al.	-/-
	18	5967661	1999-10-19	Renken et al.	-/-
	19	5996415	1999-12-07	Stanke et al.	-/-
_	-20-	6062729	2000-05-16-	Ni et al.	ARRAY CIRO
	21	6082892	2000-07-04	Adel et al.	-/-
	22	6112595	2000-09-05	Stanke et al.	-/-
	23	6174080	2001-01-16	Jennings	-/-
	24	6179466	2001-01-30	Peuse et al.	-/-
V.	25	6182510	2001-02-06	Stanke et al.	-/-
50	26	6481886	2002-11-19	Narendrnath et al.	-/-

OTHER DOCUMENTS

Examiner Initials	Cite No.	Description	****************	Т
500	27	Hirscher, Hans, "Electrostatic Chuck to Boost Your Yield", http://semiconductors.unaxis.com/en/chiponline 72dpi/issue5/c5p39 72.pdf	(NO DAY)	
200	28		(no Done)	
200	29	"DRS-1000 TM vs. Other Techniques", http://www.thermionics.com/drs/drsvsp	ory.htm (No	DAT

Ser. No. 10/720,839

Examiner: Stanley J. Parchie, & considered 5/16/05

IDS Page 1 of 2 ATCH TO: 2005 05/16

	1				
50	30	"Chapter 6: Thermal Mass", \(\psi \ PA \re\)			
\\ \mathcal{O} \\ \\ \\ \\ \\ \\ \\ \\ \\ \\ \\ \\ \\	_[http://www.seav.vic.gov.au/ftp/buildings/5starhousing/ESHousingManualCh06.pdf	_		
1	31	Ellingboe, Bert, "Plasma Processing in the Microelectronics Industry", (NO DATE)			
	1	http://www.physics.dcu.ie/~jpm/seminars/seminars00_01/intro_to_plasma_processing.PDF			
	32	"In-Situ 4000 White Paper - Solving the problems of pyrometry and thickness			
		measurement during MBE and MOCVD", (No DATE)	Ì		
		http://www.svta.com/products/monitoring/IS4K White%20Paper.pdf			
	33	Thevenard, Laura, "Wafer Temperature Measurement by Infrared Spectroscopy", Ecole			
		Polytechnique Promotion X2000, Rapport De Stage D'Option Scientifique (NO DAY)			
	34	Riebau, Rhianna A., « Photoluminescence Spectroscopy of Strained InGaAs/GaAs			
		Structures », Thesis Paper, 2001 (No MONTH)			
V	35	"Module 4: System Overview", Etch Systems – Unity II: Field Engineer Level 1 / No 0476	e)		
	36	U.S. Patent Application No.: 10/608,091	-/		
<-0		File Date: June 30, 2003	1		
20		Attorney Docket Number: 015290-682			
		Inventor: Steger			

Examiner Signature	Stanleys. Pruchared C	Date 2005 MAY 16

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